



INTERNATIONAL JOURNAL OF ENGINEERING SCIENCES & RESEARCH TECHNOLOGY

High Performance AlGa_N Metal-Semiconductor-Metal Ultraviolet Photo Detectors

S. Benzeghda^{*1}, F. Hobar², D. Decoster¹

^{*1} IEMN-Avenue Poincaré - BP 60069 59652 Villeneuve d'Ascq Cedex France

² Microsystems and Instrumentation Laboratory, Department of Electronics, University Mentouri
Constantine Route Ain El Bey, 25000, Algeria

benzeghdasabah@gmail.com

Abstract

In this paper, we present Al_{0.25}Ga_{0.75}N ultraviolet Schottky barrier photodetectors on Al₂O₃, that was modeled using The two-dimensional device simulator Silvaco and ATLAS. It was found that the device has very low dark current, with the applied bias below 1 V, the dark current was below 16 pA and the peak responsivity of 0.07A/W was achieved at 308nm. We have performed a comparison between our modeling and the experimental results.

Keywords: Photodetector, MSM, ultraviolet Schottky barrier photodetectors

Introduction

Nitride-based materials are recognized as very promising candidates for the fabrication of semiconductor photodetectors PDs in the UV spectral [1, 2]. The bandgap energy of Al_xGa_{1-x}N can be adjusted by changing Al content to match up requisite detector cut off wavelength. Various types of AlGa_N based detectors have been proposed such as p-n junctions, PIN diodes, Schottky barrier detectors and photoconductors [3]. The wide direct bandgap provides an intrinsic visible blindness, which is a critical advantage for a number of applications [1] and can operate under severe conditions (high temperature and energy levels) [3]. Among these structures, MSM photodetectors has a special place. It is a planar photodiode based on simple technology, it is easy to integrate [2], it has fast response, small capacitance and dark current, as well as large active device area [2]. It consists of two Schottky electrodes, often interlinked in the form of a comb structure, leaving a free semiconductor surface between the two contacts which forms the active region in which light will be absorbed [2, 4].

The substrate choice is one of the key issues in nitride semiconductor. Aluminum nitride (AlN), with ultra-low dislocation density are very promising for use in III-nitride epitaxial growth required for ultraviolet (UV), gallium nitride (Ga_N) and sapphire (Al₂O₃) are potential candidates which are all under investigation [5].

The active detector was a 3 μm thick unintentionally doped AlGa_N layer which was grown on top of a 10 nm thick AlN buffer layer and the AlN buffer layer was on a 1 μm thick Ga_N. The electrode fingers are

5 μm wide, and with a 5 μm spacing gap. A 200 nm thick Au was deposited [6]

Modeling Software

In comparison with an exclusive experimental procedure for this optimization the TCAD (Technology Computer Aided Design) methodology exhibits the advantages of reduced development costs and development time [7]. ATLAS is a physically-based two and three dimensional device simulator. It predicts the electrical characteristics of physical structures by simulating the transport of carriers through a two-dimensional grid. [3]. ATLAS was used also to extract the optical characteristics such external quantum efficiency, responsivity, and frequency response characteristics when the photodetector is illuminated [7].

To obtain an accurate structure and mesh description for device simulation, the following procedure is used. The Mesh is basically a two dimensional grid that covers the domain of physical simulation [8]. An important step in achieving accurate performance simulations for the device is incorporation of well documented material parameters and their dependences, like that of mobility on the doping level.

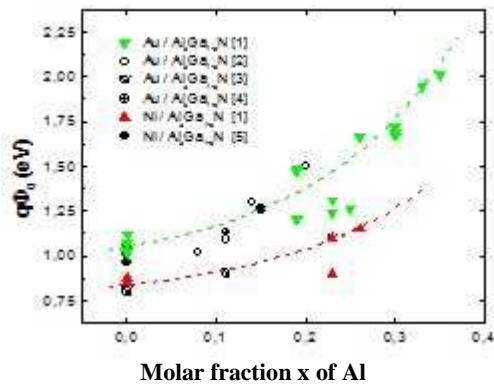


Figure 1. Variation of the height of the Schottky barrier as a function of the molar fraction of Al [2] (1)=[9], (2)=[10], [3]=[11], (4)=[12], (5)=[13]

The nature of the metal used to fabricate the Schottky diode and the excitation wavelength, for values situated both above and below the bandgap energy of the semiconductor. The decrease in the response coefficient observed when the fraction x of aluminum increases Fig. 1.

The schematic illustration about the structure was shown in Figure 2.

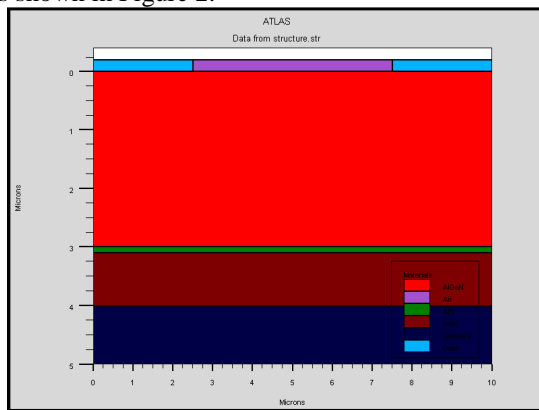


Figure 2. : MSM photodetector structure

Results and Discussion

ATLAS was used to obtain the electrical characteristics of the simulated device. Figure 3 shows the I–V curve of the photodetector. The dark current was lower than 16 pA at 1 V bias. The current transport in metal-semiconductor contacts is due mainly to majority carriers, in contrast to p-n junctions where the minority carriers are responsible. The five processes are (1) emission of electrons from the semiconductor over the potential barrier into the metal, (2) quantum mechanical

tunneling of electrons through the barrier (3) recombination in the space-charge region (4) diffusion of electrons in the depletion region, and (5) holes injected from the metal that diffuse into the semiconductor [4].

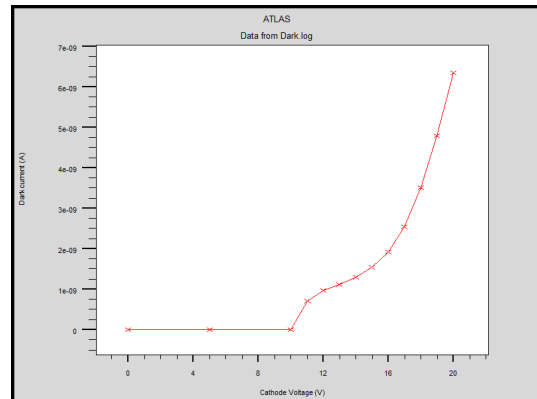


Figure 3. The I–V curve of the Al_{0.25}Ga_{0.75}N MSM photodetector in dark

The low dark current show the high quality Al_{0.25}Ga_{0.75}N layer and good Schottky contacts.. This current will improve and make a significant contribution to the signal-to-noise ratio, the different sources of noise in MSMs, as in other photodetectors, are thermal noise, 1/f^α noise and shot noise.

Fig. 3 shows the simulated distribution of the electric field of the photodetector in obscurity. If the bias voltage is sufficiently high, the region between the electrodes is completely depleted and this produces an electric field.

The peak electric field of the is 7.81*10⁴V/cm.

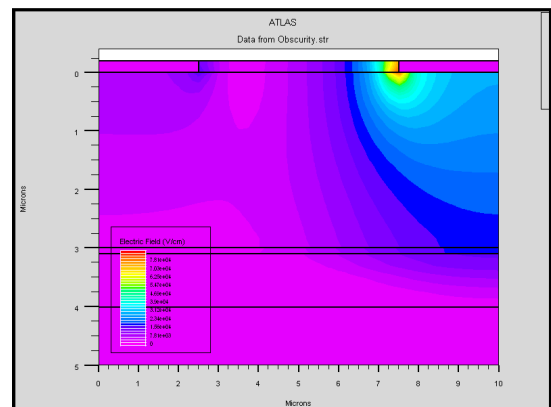


Figure 4. Electric Field distribution in Dark

We illuminate the device at 300 nm, Fig 5, 6. Present the I–V curve and the distribution of electrical field respectively.

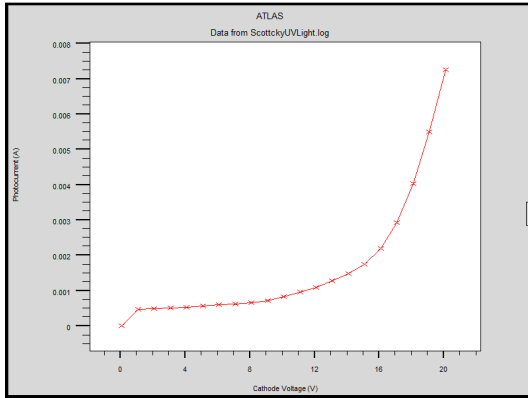


Figure 5. The I-V curve of the Al_{0.25}Ga_{0.75}N MSM photodetector under illumination

The absorption of light near the reverse-biased junction creates electron-hole pairs which are separated under the effects of the electric field. The photocurrent/dark current rejection is more than five orders of magnitude.

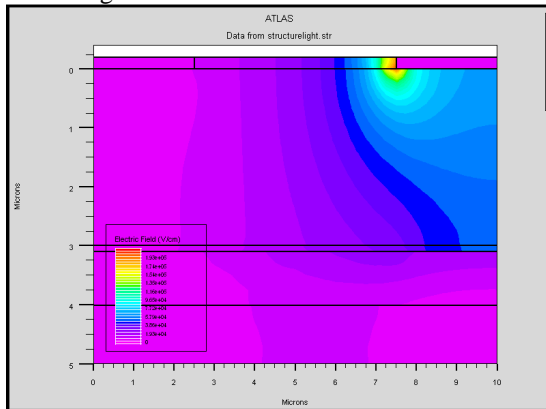


Figure 6. Electric Field distribution under illumination

Figure 7 shows the spectral responsivity of a Al_{0.25}Ga_{0.75}N UV photodetector under 1 V bias, the peak responsivity is found at 308nm, and it achieved about 0.07 A/W.

We calculated also the the responsivity under 1, 2, 4 and 6 bias V. There is a good linear relationship between the peak responsivity and bias voltage Figure. 8.

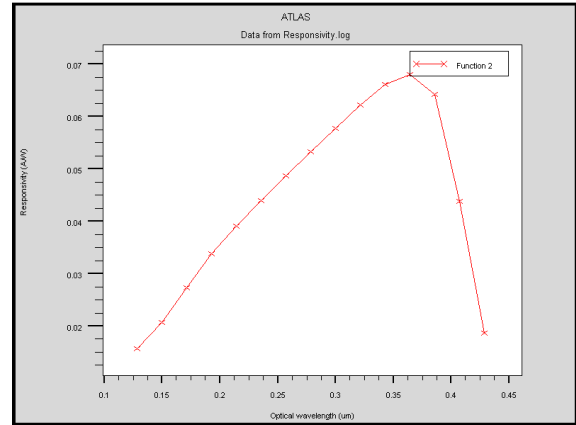


Figure 7. Spectral responsivity of a Al_{0.25}Ga_{0.75}N UV photodetector under 1 V bias.

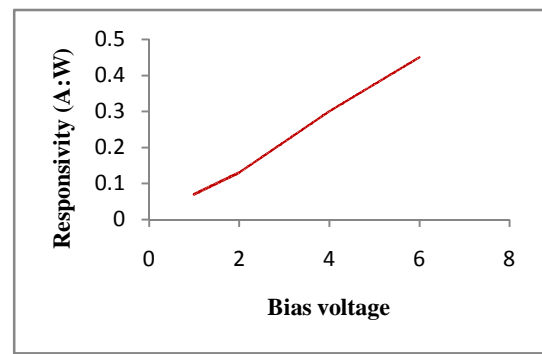


Figure 8. The peak responsivity as a function of bias voltage.

The NEP is defined as the incident optical power for which the signal-to-noise ratio is 1, and hence the photocurrent I_{ph} is equal to the noise current I_b . In other words, it is the smallest optical power which can be measured. It follows that the NEP parameter is given by the equation: $NEP = I_b/R$, where R is the measured responsivity, and we calculated I_b as [6]:

$$\langle I_b^2 \rangle = (4k_b T/R_{dark} + 2qI_{dark})\Delta f \dots\dots (1)$$

We can use NEP to define the detectivity [2, 6]:

$$D = (A\Delta f)^{1/2} / NEP \dots\dots(2)$$

where A is device area. With a 1V applied bias it was found a maximum D of $4.43 \times 10^{11} \text{ cm.Hz}^{1/2}/\text{W}$ at 307nm . The detectivity of the device was higher than those ($7 \sim 50 \times 10^9 \text{ cm.Hz}^{1/2}/\text{W}$) observed from GaN-based MSM photodetectors with a similar structure [6].

Conclusions

High performance visible-blind AlGaIn-based MSM photodetectors are attractive because of their low dark current about 16 pA under 1V bias. The photocurrent/dark current rejection is more than five orders of magnitude. That can reduce noise level, and enhance the detectivity of the PDs. The experimental results [6] are in agreement with our simulations.

References

- [1] K. H. Lee, "Al_{0.25}Ga_{0.75}N/GaN Schottky Barrier Photodetectors with an Al_{0.3}Ga_{0.7}N Intermediate Layer" *Journal of The Electrochemical Society*, 156 (7) J199-J202 (2009).
- [2] Didier Decoster, Joseph Harari, *Détecteurs optoélectroniques*, Lavoisier, 2002.
- [3] Stanislav V. Averin · Petr I. Kuznetsov , "Solar-blind MSM-photodetectors based on Al_xGa_{1-x}N heterostructures", *Opt Quant Electron* (2007) 39:181–192.
- [4] S.M., *Physics of semiconductor devices*, John Wiley & Sons Ltd., New York.
- [5] Kristina M. Davitt, "Ultraviolet Light Emitting Diodes and Bio-Aerosol Sensing", Ph.D. dissertation, Brown University, 2006.
- [6] J. Li, M.Zhao, "High performance Schottky UV photodetectors based on epitaxial AlGaIn thin film", *Elsevier Physica B* 405 (2010) 996–998.
- [7] SILVACO, *Atlas user's manual, device simulation software*, 2002.
- [8] Mohan K. Chirala, "Design, Simulation and Modeling of Collector-up GaInP/GaAs Heterojunction Bipolar Transistors", Master of science thesis, Osmania University, 2002.
- [9] E.Monroy, F.Calle, J.L.Pau, F.J.Sancher, E.Munoz, F.Omnes, B.Beaumont, et P.Gibart, *J.Appl.Phys.* 88, 2081 (2000).
- [10] A.Y.Polyakov, N.B.Smirnov, , *Solid State Electron.* 42, 1959 (1998).
- [11] M.R.H.Khan, H.Nakayama, , *Solid State Electron.* 41, 287 (1997).
- [12] S.Arulkumaran, T.Egawa, G.Y.Zhao, H.Ishikawa, T.Jimbo, et M.Umeno, *Jpn.J.Appl.Phys.* 39, L351 (2000).
- [13] L.S.Yu, D.J.Qiao, Q.J.Xing, S.S.Lau, K.S.Boutros, *Appl.Phys.Lett.* 73, 238 (1998)